



Microstructure and conductivity of 8.5YSZ thin films obtained by sol-gel processing

Benjamin Butz^{1*}, H. Störmer¹, D. Gerthsen¹, M. Bockmeyer², R. Krüger², P. Löbmann², C. Peters³, A. Weber³, E. Ivers-Tiffée³
¹Laboratorium für Elektronenmikroskopie (LEM), University of Karlsruhe (TH), D-76128 Karlsruhe, Germany
²Fraunhofer-Institut für Silicatforschung ISC, D-97082 Würzburg, Germany
³Institut für Werkstoffe der Elektrotechnik (WE), University of Karlsruhe (TH), D-76128 Karlsruhe, Germany
 *contact: benjamin.butz@kth.edu

Motivation

Ionic conducting 8.5 mol% Y₂O₃-doped ZrO₂ (8.5YSZ) is used as solid electrolyte in solid oxide fuel cells (SOFCs)

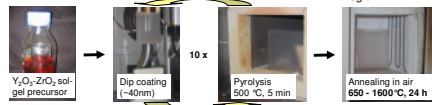
Trend: Reduction of operating temperature down to 500-700 °C

Problem: Ionic conductivity of microcrystalline 8.5YSZ too low in designated temperature range!

Idea: Enhancing ionic conductivity σ_{ion} of YSZ by decreasing mean grain size d ? [1]

Project: Investigation of the grain size effect on ionic conductivity in 8.5YSZ

Thin-film fabrication



1. Dip coating of sapphire substrates in metal-organic sol-gel precursor [2]
2. Pyrolysis to burn out the organic fraction of the sol-gel [2]
3. Additional annealing to adjust the grain size in each single sample

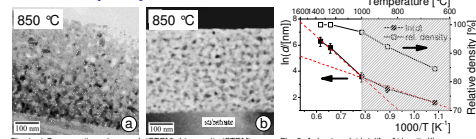
→ Series of YSZ thin films with varying mean grain size

Experimental techniques

- Investigation of chemical composition / impurities as well as crystal structure and microstructure by transmission electron microscopy (TEM)
- TEM sample preparation using standard as well as focussed ion beam (FIB) techniques (Zeiss Cross-Beam EsB 1540)

200 keV Philips CM200 FEG/ST	200 keV LEO 922 OMEGA
<ul style="list-style-type: none"> Conventional TEM (CTEM) High-resolution TEM (HRTEM) Selected-area electron diffraction (SAED) using imaging plates Energy-dispersive X-ray spectroscopy (EDXS) 	<ul style="list-style-type: none"> Scanning TEM (STEM) + high-angle angular dark-field (HAADF) detector: Z-contrast imaging

Thin-film quality



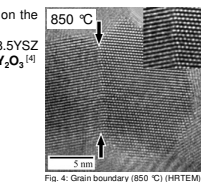
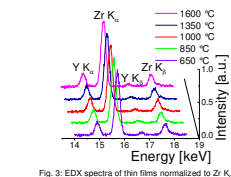
- Thin films free of cracks with well-defined thickness/mean grain size (Fig. 1a) [3,4]
- Narrow-distributed grain size d (5 nm at 650 °C to ~ 1 μ m at 1400 °C)
- Good adhesion on substrates

- Porosity in thin films annealed below 1250 °C (Fig. 1b)
- Size of pores = mean grain size

Grain growth in nano-crystalline films (annealed below 1250 °C) limited by the presence of pores as indicated by the dashed lines in Fig. 2. [4]

Stoichiometry and purity

- Final Y³⁺ dopant concentration independent on the annealing temperature (Fig. 3)
- Quantification with respect to a TOSOH 8.5YSZ thick-film electrolyte: **8.27 ± 0.33 mol% Y₂O₃** [4]



No Si/Al-rich glassy phases at the grain boundaries (HRTEM imaging + analytic methods)

Crystal structure and phases

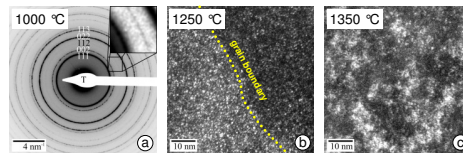


Fig. 5: a) SAED pattern of the thin film annealed at 1000 °C, b) and c) CTEM dark-field images visualizing tetragonal regions

SAED: weak additional {112} reflections (see insert in Fig. 5a)

→ Tetragonal phase ($a_x = c_x = a_y$) present in all prepared thin films

Dark-field imaging with {112} intensity:

- Homogeneously distributed tetragonal regions in samples annealed ≤ 1250 °C (Fig. 5b)
- Size of precipitates 0.5-1 nm
- Concentration of precipitates independent of grain boundary/grain core (Fig. 5b)
- Clustering of tetragonal regions in specimen annealed at 1350 °C (Fig. 5c)

YSZ thin films not completely stabilized in cubic phase, microstructure strongly dependent on the final annealing temperature. [4]

Reference material

Microcrystalline 8.5YSZ SOFC-electrolyte substrates (TOSOH powder) [5]
 as-sintered + homogenized ↔ annealed (950 °C / 2000 h)

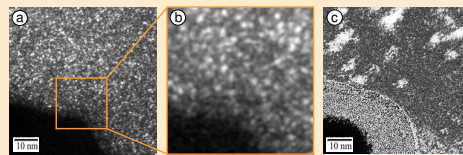


Fig. 6: CTEM dark-field images, taken using {112} reflections, of a) as-sintered 8.5YSZ, b) magnified region visualizing temporal fluctuations, c) annealed 8.5YSZ

As-sintered substrates:

- Tetragonal phase ($a_x = c_x = a_y$) clearly identified in 8.5YSZ [5]
 - Microstructure similar to thin films annealed ≤ 1250 °C (Fig. 5b, 6a)
 - Temporal fluctuation of tetragonal regions (Fig. 6b), suppression by LN₂-cooling
- No cation-diffusion based process!

Annealed substrates:

- Clustering of tetragonal regions (Fig. 6c) + fluctuating regions [5]
- Slight variations (about ±10 at%) of Y-content observed on nano-scale applying electron energy loss spectroscopy (EELS)

→ Decomposition?

8.5YSZ not stabilized in cubic phase, fluctuating microstructure in as-sintered electrolytes, clustering of tetragonal regions during annealing at 950 °C. [5]

Phase diagram

Thin films annealed ≤ 1250 °C + as-sintered 8.5YSZ substrates:

- Temporal fluctuation of tet. regions
 - "Small" energetic gap between Gibbs free-energy functions of t¹-c-phase in wide range of Y³⁺-content (Fig. 8 Ⓢ)
- Formation of metastable t¹-phase

Thin film annealed at 1350 °C + annealed 8.5YSZ substrates:

- Pinning + clustering of tet. regions
- No obvious growth
- Local variation of Y content on nm-scale

→ Clustered tet. regions t¹-phase? Decomposition at higher T, t? (Driving force, mechanism, reason for Pinning)

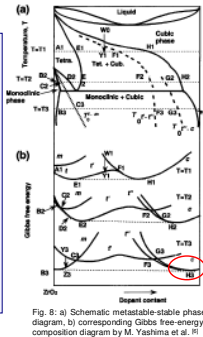


Fig. 8: a) Schematic metastable-stable phase diagram, b) corresponding Gibbs free-energy-composition diagram by M. Yashima et al. [6]

Conductivity

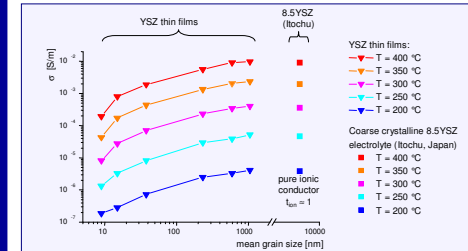


Fig. 9: DC conductivity of thin films versus mean grain size

DC conductivity:

- Coincidence of total DC conductivity of microcrystalline (1350 °C, 1250 °C) thin films with ionic conductivity of microcrystalline 8.5YSZ thick-film electrolytes (Itochu)
- Decreasing total conductivity with decreasing mean grain size

Impedance spectroscopy:

- Total resistance governed by grain boundary process (Fig. 9)

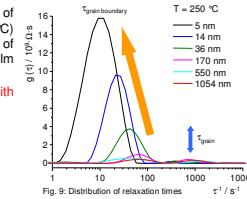


Fig. 9: Distribution of relaxation times

Summary

- YSZ thin films with 8.27 ± 0.33 mol% Y₂O₃ prepared by sol-gel process
- Grain size (5 nm – 1 μ m) / degree of porosity adjustable by annealing
- Residues of the sol-gel process / impurities in the thin films not detectable

Structure

- YSZ thin films not completely stabilized in the cubic phase: temporal fluctuations indicative for the existence of the metastable t¹-phase
- Clustering of the observed tetragonal regions at higher temperature and longer time is still not completely understood. First EELS experiments on the nano-scale show slight fluctuations of the Y content.

→ The presence of the tetragonal phase as well as the resulting microstructure have to be taken into account in modeling the electrical transport properties, since a strong influence of tetragonal nano-scaled regions in 8.5YSZ on ionic conductivity is observed! [5]

Conductivity

- Conductivity of microcrystalline YSZ thin films similar to standard electrolyte
- Reduction of conductivity by decreasing the mean grain size down to nano-scale, total resistance governed by grain boundary process!
- Clustered tetragonal regions as reason for degradation of bulk conductivity: Y₂ and V_o^{••}-depleted regions as scattering regions for O²⁻ hopping? Pinning of free V_o^{••} in clustered regions?

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